


PALM INTRANET

 Day : Monday
 Date: 3/8/2004
 Time: 14:53:01

Inventor Information for 10/627894

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SHIOTA, ATSUSHI	USHIKU	JAPAN

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Inventor Name Search Result

Your Search was:

Last Name = SHIOTA

First Name = ATSUSHI

Application#	Patent#	Status	Date Filed	Title	Inventor Name 21
10726666	Not Issued	020	12/04/2003 all	INSULATION FILM <i>Product & Comp</i> <i>no pore pub</i>	SHIOTA, ATSUSHI <i>IFW</i>
10427894	Not Issued	030	07/24/2003	FLUORINE-FREE PLASMA CURING PROCESS FOR POROUS LOW-K MATERIALS	SHIOTA, ATSUSHI
10346560	Not Issued	030	01/17/2003	FLUORINE-FREE PLASMA CURING PROCESS FOR POROUS LOW-K MATERIALS	SHIOTA, ATSUSHI
10307384	Not Issued	168 <i>ab</i>	12/02/2002	PROCESS FOR PRODUCING SILICA-BASED FILM, SILICA-BASED FILM, INSULATING FILM, AND SEMICONDUCTOR DEVICE	SHIOTA, ATSUSHI
10278066	Not Issued	168 <i>ab</i>	10/15/2002	PROCESS FOR PRODUCING SILICA-BASED FILM, SILICA-BASED FILM, INSULATING FILM, AND SEMICONDUCTOR DEVICE	SHIOTA, ATSUSHI
10255941 <i>2003077746</i>	Not Issued	071 <i>ab</i>	09/27/2002	STACKED FILM, INSULATING FILM AND SUBSTRATE FOR SEMICONDUCTOR	SHIOTA, ATSUSHI <i>IFW</i>
10252607 <i>2003077508</i>	Not Issued	041 <i>ab</i>	09/24/2002 <i>428417</i>	METHOD OF FILM FORMATION, INSULATING FILM, AND SUBSTRATE FOR SEMICONDUCTOR	SHIOTA, ATSUSHI <i>IFW</i>
10252606 <i>1/2 prod; 1/2 process</i>	Not Issued	090 <i>ab</i>	09/24/2002 <i>428417</i>	STACKED FILM, METHOD FOR THE FORMATION OF STACKED FILM, INSULATING FILM, AND SUBSTRATE FOR SEMICONDUCTOR	SHIOTA, ATSUSHI <i>FFW</i>
10165324	Not Issued	071 <i>ab</i>	06/10/2002	METHOD FOR THE FORMATION OF SILICA FILM, SILICA FILM, INSULATING FILM, AND SEMICONDUCTOR DEVICE	SHIOTA, ATSUSHI <i>IFW</i>
10103996 <i>Comp. for prod. Comp.</i>	Not Issued	041 <i>ab</i>	03/25/2002 <i>427387</i>	COMPOSITION FOR FILM FORMATION, METHOD OF FILM FORMATION, AND SILICA-BASED FILM	SHIOTA, ATSUSHI <i>IFW</i>
10094647	Not Issued	041	03/12/2002	METHOD OF FORMING DUAL DAMASCENE STRUCTURE	SHIOTA, ATSUSHI <i>IFW</i>
10014593	6558747	150	12/14/2001	METHOD OF FORMING INSULATING FILM AND PROCESS FOR PRODUCING SEMICONDUCTOR DEVICE	SHIOTA, ATSUSHI
09778822	6406794	150	02/08/2001	FILM-FORMING COMPOSITION	SHIOTA, ATSUSHI
09770289	Not Issued	041 <i>ab</i>	01/29/2001	PROCESS FOR PRODUCING SILICA-BASED FILM, SILICA-BASED FILM, INSULATING FILM, AND SEMICONDUCTOR DEVICE	SHIOTA, ATSUSHI <i>IFW</i>
09670547	6410151	150	09/27/2000	COMPOSITION FOR FILM FORMATION, METHOD OF FILM FORMATION, AND INSULATING FILM	SHIOTA, ATSUSHI
09669859	6410150	150	09/27/2000	COMPOSITION FOR FILM FORMATION, METHOD OF FILM FORMATION, AND INSULATING FILM	SHIOTA, ATSUSHI
09163008	6190833	150	09/30/1998	RADIATION-SENSITIVE RESIN COMPOSITION	SHIOTA, ATSUSHI

<u>09126953</u>	Not Issued	161 <i>sh</i>	07/31/1998	LAMINATED MATERIAL FOR MULTI-LAYERED PRINTED CIRCUIT BOARDS AND MULTI-LAYERED PRINTED CIRCUIT BOARD USING THE SAME	SHIOTA , ATSUSHI
<u>08713875</u>	5773178	150	09/13/1996	PROCESS FOR PRODUCING A PATTERNED ANISOTROPIC POLYMERIC FILM	SHIOTA , ATSUSHI
<u>08510867</u>	5811504	150	08/03/1995	LIQUID CRYSTALLINE EPOXY MONOMER AND LIQUID CRYSTALLINE EPOXY RESIN CONTAINING MESOGEN TWINS	SHIOTA , ATSUSHI
<u>08023471</u>	Not Issued	166	02/25/1993	RESIN COMPOUND	SHIOTA , ATSUSHI

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ND
JO
 Inventor Search Completed: No Records to Display.

Search Another: Inventor	Last Name <input type="text" value="shiota"/>	First Name <input type="text" value="atsushi"/>
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from overlapping case

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Inventor Name Search Result

Your Search was:

Last Name = ALBANO

First Name = RALPH

Application#	Patent#	Status	Date Filed	Title	Inventor Name 5
10627894	Not Issued	030	07/24/2003	FLUORINE-FREE PLASMA CURING PROCESS FOR POROUS LOW-K MATERIALS	ALBANO, RALPH
10346560	Not Issued	030	01/17/2003	FLUORINE-FREE PLASMA CURING PROCESS FOR POROUS LOW-K MATERIALS	ALBANO, RALPH
09952649	Not Issued	061	09/14/2001	PLASMA CURING PROCESS FOR POROUS LOW-K MATERIALS	ALBANO, RALPH
09952398	Not Issued	071	09/14/2001	ULTRAVIOLET CURING PROCESS FOR POROUS LOW-K MATERIALS	ALBANO, RALPH
09906276	Not Issued	071	07/16/2001	PLASMA CURING OF MSQ-BASED POROUS LOW-K FILM MATERIALS	ALBANO, RALPH

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albano

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ralph

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